## UNITED STATES PATENT AND TRADEMARK OFFICE **CERTIFICATE OF CORRECTION**

PATENT NO. : 7,338,856 B2 APPLICATION NO.: 10/649050

DATED INVENTOR(S) : March 4, 2008

: Chen et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

In column 10, lines 56-58, in Claim 8, delete "introducing dopant atoms of the first type of dopant material into the first polysilicon layer" and insert -- forming the first polysilicon layer --, therefor.

Signed and Sealed this

Page 1 of 1

Sixth Day of January, 2009

JON W. DUDAS Director of the United States Patent and Trademark Office